

Application No.: 09/847,111**Docket No.: 4824-041****AMENDMENTS TO THE CLAIMS:**

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

1-26. (Cancelled)

27. (New) A measuring system of a gas-stream environment, said measuring system of a gas-stream environment comprising:

a stage, said stage is located on a transport apparatus and a wafer placed on said stage;

a datum platen, said datum platen is located on said transport apparatus and on stage to place a datum slice, wherein said datum slice to be the measuring reference point;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, said second gas nozzle is located on a side of said stage;

a first tube, said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, said second tube is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to make said gas that passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas

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nozzle to form a gas stream;

a transport slot, said transport slot is collected said gas in said gas stream, and used as a channel to exhaust said gas stream; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport slot by using a third tube, wherein said gas supplier and said gas-exhausting apparatus must be opened continuously in said measuring process.

28. (New) The measuring system of a gas-stream environment according to claim 27, further comprising a first flow rate regulating valve fixing on said first gas nozzle.

29. (New) The measuring system of a gas-stream environment according to claim 27, further comprising a second flow rate regulating valve fixing on said second gas nozzle.

30. (New) The measuring system of a gas-stream environment according to claim 27, wherein said gas-extracting apparatus comprises a gas-extracting motor.

31. (New) The measuring system of a gas-stream environment according to claim 27, wherein said gas-extracting apparatus comprises a venture structure.

32. (New) The measuring system of a gas-stream environment according to claim 27, wherein said gas is an inert gas.

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33. (New) The measuring system of a gas-stream environment according to claim 27, wherein said gas is nitrogen.

34. (New) A measuring system of a gas-stream environment, said measuring system of a gas-stream environment comprising:

a stage, said stage is located on a transport apparatus and a wafer placed on said stage;

a datum platen, said datum platen is located on said transport apparatus and on a side of said stage to place a datum slice;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, said second gas nozzle is located on a side of said stage;

a first tube, said first tube is connected with said first gas nozzle and with said supplier;

a second tube, said second tube is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to make said gas passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, said transport slot is extracted said gas; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport

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slot by using a third tube, wherein said gas supplier and said gas-exhausting apparatus must be opened continuously in said measuring process.

35. (New) The measuring system of a gas-stream environment according to claim 34, wherein said first tube comprises a first flow rate regulating valve.

36. (New) The measuring system of a gas-stream environment according to claim 34, wherein said second tube comprises a second flow rate regulating valve.

37. (New) The measuring system of a gas-stream environment according to claim 34, wherein said gas-extracting apparatus comprises a gas-extracting motor.

38. (New) The measuring system of a gas-stream environment according to claim 34, wherein said gas-extracting apparatus comprises a venture structure.

39. (New) The measuring system of a gas-stream environment according to claim 34, wherein said gas is an inert gas.

40. (New) The measuring system of a gas-stream environment according to claim 34, wherein said gas is a nitrogen.

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41. (New) A measuring system of a gas-stream environment, said measuring system comprising:

a stage, said stage is located on a transport apparatus and a wafer placing on said stage;

a datum platen, said datum platen is located on said transport apparatus and on a side of said stage to place a datum slice;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas in a gas stream;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen and on said transport apparatus to exhaust said gas;

a second gas nozzle, said second gas nozzle is located on a side of said stage and on said transport apparatus to exhaust said gas in said gas stream;

a first tube, said first tube having a first flow rate regulating valve, and is connected with said first gas nozzle and with said gas supplier;

a second tube, said second tube having a second flow rate regulating valve and is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to make said gas that passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport slot by using a third tube and is produced an attraction to remove said gas, wherein said gas supplier and said gas-exhausting apparatus must be opened continuously in said measuring process.

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42. (New) The measuring system of a gas-stream environment according to claim 41, wherein said gas-extracting apparatus comprises a venture structure.

43. (New) The measuring system of a gas-stream environment according to claim 41, wherein said gas is an inert gas.

44. (New) The measuring system of a gas-stream environment according to claim 41, wherein said gas is nitrogen.

45. (New) The measuring system of a gas-stream environment according to claim 27, wherein said first gas nozzle used to exhaust a gas in a gas stream.

46. (New) The measuring system of a gas-stream environment according to claim 27, wherein said transport slot used collect said gas in said gas stream.

47. (New) The measuring system of a gas-stream environment according to claim 27, wherein said transport slot used to be a channel to exhaust said gas in said gas stream.

48. (New) The measuring system of a gas-stream environment according to claim 27, wherein the step of said lens located above said stage to measure said thickness of said wafer

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comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.

49. (New) The measuring system of a gas-stream environment according to claim 34, wherein the step of said lens located above said stage to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.

50. (New) The measuring system of a gas-stream environment according to claim 41, wherein the step of said lens located above said stage to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

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irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.